

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4617	((phas\$3 or shift\$3) near2 (mask or photomask or reticle) or \$3PSM).ti, ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:32
L2	819	1 and ((attenuat\$3 or halftone or half tone) with (phas\$3 or shift\$3 or PS or \$3PSM) or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:33
L3	233	2 and ((etch\$3 or groov\$3 or recess\$3 or mesa or rais\$3 or thick\$4) with (phas\$3 or shift\$3 or PS or \$3PSM) or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:36
L4	109	3 and ((blank or wavelength or wave length) with (phas\$3 or shift\$3 or mask or photomask or reticle or PS or \$3PSM) or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:39
L5	8782	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:40
L6	422	216/12.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:40
L7	55	3 and (5 or 6) not 4	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:40
L8	240	2 and (5 or 6) not 4 not 7	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:43
L9	13	8 and (reactive ion near2 etch\$3 or RIE) with ("SF.sub.6" or "CF.sub.4" or sulfur hexafluoride or carbon tetrafluoride)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:42
L10	2	2 and (reactive ion near2 etch\$3 or RIE) with ("SF.sub.6" or "CF.sub.4" or sulfur hexafluoride or carbon tetrafluoride) not 4 not 7 not 9	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:45
L11	2	3 and ((blank or wavelength or wave length) with (phas\$3 or shift\$3 or mask or photomask or reticle or PS or \$3PSM) or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM) not 4 not 7 not 9 not 10	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:49

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L12	1	3 and ((second or third or plural or multiple) with (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or mask or photomask or reticle or PS or \$3PSM) or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM).ti,ab. not 4 not 7 not 9 not 10 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:51
L13	4	3 and ((second or third or plural or multiple) same (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or mask or photomask or reticle or PS or \$3PSM) or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM).ti,ab. not 4 not 7 not 9 not 10 not 11 not 12	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:52
L14	5	2 and ((second or third or plural or multiple) same (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or mask or photomask or reticle or PS or \$3PSM) or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM).ti,ab. not 4 not 7 not 9 not 10 not 11 not 12 not 13	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 09:53
L15	140	2 and ((second or third or plural or multiple) same (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or mask or photomask or reticle or PS or \$3PSM) or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM) not 4 not 7 not 9 not 10 not 11 not 12 not 13 not 14	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 10:03
L16	79	15 and ((transmi\$6 or transpar\$6) same ((attenuat\$3 or halftone or half tone) same (phas\$3 or shift\$3 or \$3PSM)) or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 10:02
L17	7	((Cheng Ming or ChengMing) near2 Lin).in. not 4 not 7 not 9 not 10 not 11 not 12 not 13 not 14 not 16	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 10:04
L18	579	(5 or 6) and (attenuat\$3 or halftone or half tone or semitranspar\$6 or semitransmi\$6 or semi (transpar\$6 or transmi\$6) or partial\$2 (transpar\$6 or transmi\$6) or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 10:11

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L19	22	18 and ((wavelength or wave length) and (thick\$4 or depth or height)).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 10:13
L20	58	18 and (wavelength or wave length).ti,ab. not 19	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 10:15
L21	148	18 and (transmit\$5 or transmis\$8 or transparen\$4) same (equation or expression or formula)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 10:20
L22	161	18 and (phas\$3 or shift\$3 or PS or \$3PSM) same (equation or expression or formula)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 10:21
L23	116	21 and 22	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 10:21
L24	19	(mask or photomask or reticle or \$3PSM) near3 blank same (different or other or another or plural or multiple) near3 (company or organization or corporation or enterprise or establishment or firm or outfit or crafter or business or fabricator or creator or builder or producer or assembler or manufacturer or maker or supplier)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 11:18
L25	0	(((phas\$3 or shift\$3 or \$3PS) near2 (mask or photomask or reticle) or \$3PSM) and (attenuat\$3 or halftone or half tone or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM) and (wavelength or wave length) and blank and etch\$3 and (transmit\$5 or transmis\$8 or transparen\$4) and (light\$3 or radiat\$3) and thickness and (company or organization or corporation or enterprise or establishment or firm or outfit or crafter or business or fabricator or creator or builder or producer or assembler or manufacturer or maker or supplier)).clm.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 11:22

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L26	9	(((phas\$3 or shift\$3 or \$3PS) near2 (mask or photomask or reticle) or \$3PSM) and (attenuat\$3 or halftone or half tone or attPSM or att PSM or HPSM or H PSM or HTPSM or HT PSM) and (wavelength or wave length) and blank and etch\$3 and (transmit\$5 or transmis\$8 or transparen\$4) and (light\$3 or radiat\$3) and thickness).clm.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/05/04 11:22
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